

Abstract

A method for fabricating an integrated optical isolator includes depositing a wire grid material on a magneto-optical substrate and depositing a resist film on the wire grid material. The method further includes bringing a mold with a wire grid pattern in contact with the resist film and compressing the mold and resist film together so as to emboss the wire grid pattern in the resist film. The method further includes transferring the wire grid pattern in the resist film to the wire grid material on the magneto-optical substrate by etching.